

WHAT IS CLAIMED IS:

1. A liquid crystal panel substrate comprising:
 reflecting electrodes formed on a substrate;
 a switching element formed corresponding to each of the reflecting electrodes;
 a passivation film formed on said reflecting electrodes comprising a silicon oxide film; and
 a silicon nitride film formed as an insulating interlayer between said reflecting electrodes and a metal layer thereunder having moisture resistance.
2. A liquid crystal panel substrate according to claim 1, wherein said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprises a silicon nitride film and a silicon oxide film, and has a laminate structure in which said silicon nitride film is formed on said silicon oxide film.
3. A liquid crystal panel substrate comprising:
 a pixel region having a matrix of reflecting electrodes formed on a substrate and a switching element formed corresponding to each of said reflecting electrodes, a periphery region of said pixel region on the substrate having a metal layer and an insulating interlayer; and
 a passivation film having a laminate structure comprising a silicon oxide film and a silicon nitride film on said silicon oxide film, the passivation film being formed at edge sections of the metal layer and the insulating interlayer.
4. A liquid crystal panel substrate comprising:
 a pixel region having a matrix of reflecting electrodes formed on a substrate and a transistor formed corresponding to each of the reflecting electrodes;
 a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region;

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a first passivation film comprising a silicon oxide film formed on said reflecting electrodes in said pixel region; and
a second passivation film comprising a silicon nitride film formed on said periphery region.

5. A liquid crystal panel substrate according to claim 4, the silicon nitride film being a first silicon nitride film, the liquid crystal panel substrate further comprising a second silicon nitride film as an insulating interlayer provided between said reflecting electrodes and a metal layer thereunder.

6. A liquid crystal panel substrate according to claim 5, the silicon oxide film being a first silicon oxide film, said insulating interlayer between said reflecting electrodes and said metal layer thereunder comprising the second silicon nitride film and a second silicon oxide film, and having a laminate structure in which said second silicon nitride film is formed on said second silicon oxide film.

7. A liquid crystal panel substrate comprising:
a pixel region having a matrix of reflecting electrodes formed on a substrate and transistor formed corresponding to each of the reflecting electrodes;
a peripheral circuit arranged in a periphery region of said pixel region on the substrate for supplying signals to said transistors in said pixel region, the periphery region having a metal layer and an insulating layer;

a first passivation film comprising a first silicon oxide film formed in said pixel region; and

a second passivation film having a laminate structure comprising a second silicon oxide film and a silicon nitride film formed on the second silicon oxide film, the second passivation film being formed at edge sections of the metal layer and the insulating interlayer.

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8. A liquid crystal panel substrate according to claim 3, further comprising a seal material formed on said silicon nitride film for sealing with a counter substrate.

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9. A liquid crystal panel substrate according to claim 3, said edge section of said metal layer and the insulating interlayer being a scribed region of the substrate.

10. A liquid crystal panel substrate comprising:
a pixel region having reflecting electrodes formed on a semiconductor substrate and a switching element formed corresponding to each of the reflecting electrodes;
and
a passivation film formed by a silicon nitride film having moisture resistance and formed on a scribed region of said semiconductor substrate.

11. A liquid crystal panel substrate according to claim 10, said passivation film having a laminate structure comprising a silicon oxide film and the silicon nitride film formed on the silicon oxide film.

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12. A liquid crystal panel comprising a first substrate, a second substrate opposed to the first substrate, a liquid crystal therebetween, and a seal material sealing the first substrate and the second substrate, the liquid crystal panel further comprising:
a pixel region having reflecting electrodes formed on said first substrate; and
a passivation film comprising a silicon nitride film formed in a region arranged with said seal material on said first substrate, the seal material being formed on the silicon nitride.

13. A liquid crystal panel according to claim 12, the passivation film being a first passivation film and the liquid crystal panel further comprising a second passivation film comprising a silicon oxide film formed on the reflecting electrodes.

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